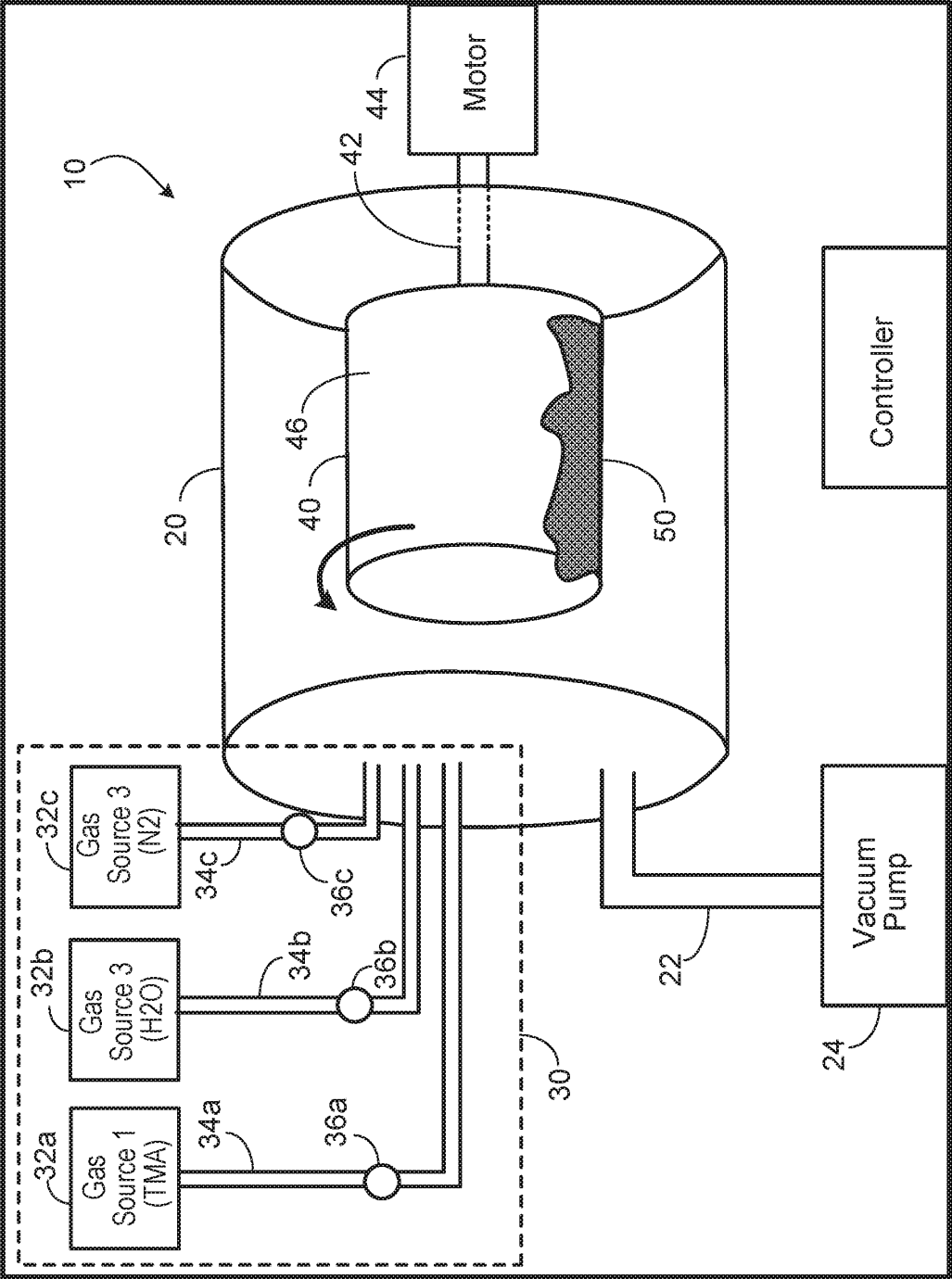




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	Metal Precursor Dosing	Purge 1	Oxidizer Dosing	Purge 2
Fill Pressure	0.1 Torr to 0.5x $P_{\text{saturation, Metal}}$	1 Torr to 100 Torr	0.1 Torr to 0.5x $P_{\text{saturation, ox}}$	1 Torr to 100 Torr
Hold Time	1 s to 600 s	1 s to 600 s	1 s to 600 s	1 s to 600 s
Pump Pressure	< 1 Torr (50 mTorr typical)	< 1 Torr (50 mTorr typical)	< 1 Torr (50 mTorr typical)	< 1 Torr (50 mTorr typical)
Number of Repeats	Determine by reactor volume, pressure, & powder surface area (1-10 typical)	1 to 10 typical. Higher gives more ALD-like deposition. Lower gives more CVD.	Determine by reactor volume, pressure, & powder surface area (1-10 typical)	1 to 10 typical. Higher gives more ALD-like deposition. Lower gives more CVD.

FIG. 2

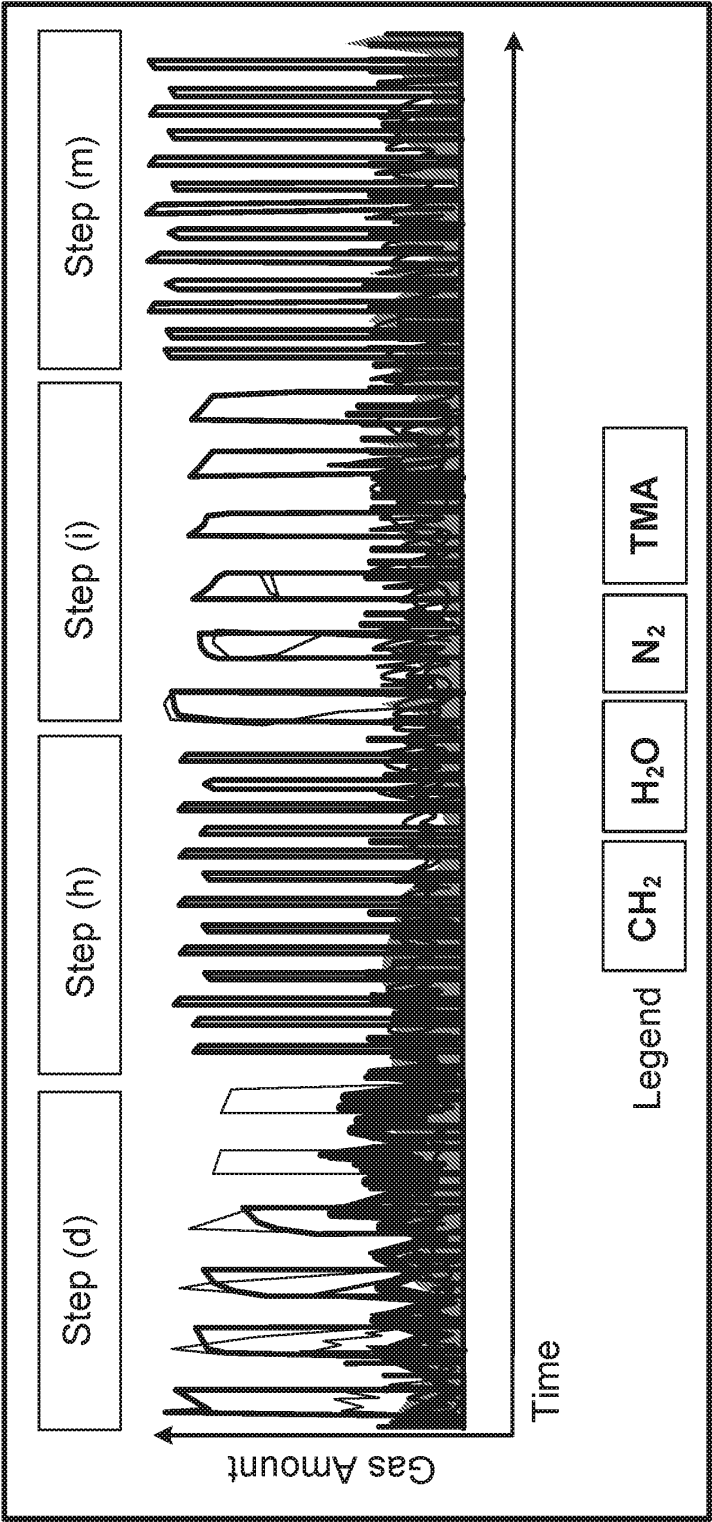


FIG. 3